

RESPONSE UNDER 37 C.F.R. § 1.116
EXPEDITING PROCEDURE
EXAMINING GROUP 1700

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Wunnicke, <i>et al.</i>	Docket No.:	INF 2004 SP 00138 US
Serial No.:	10/781,920	Art Unit:	1795
Filed:	February 20, 2004	Examiner:	Brittany L. Raymond
For:	Method for Fabricating a Resist Mask for Patterning Semiconductor Substrates		

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE UNDER 37 CFR § 1.116

Dear Sir:

Applicant respectfully submits the following remarks in response to Examiner's Office Action dated January 2, 2008, which Action was made final. Applicant respectfully requests that these remarks be entered in pursuant to the provisions of 37 CFR § 1.116, and respectfully request reconsideration of the claims.